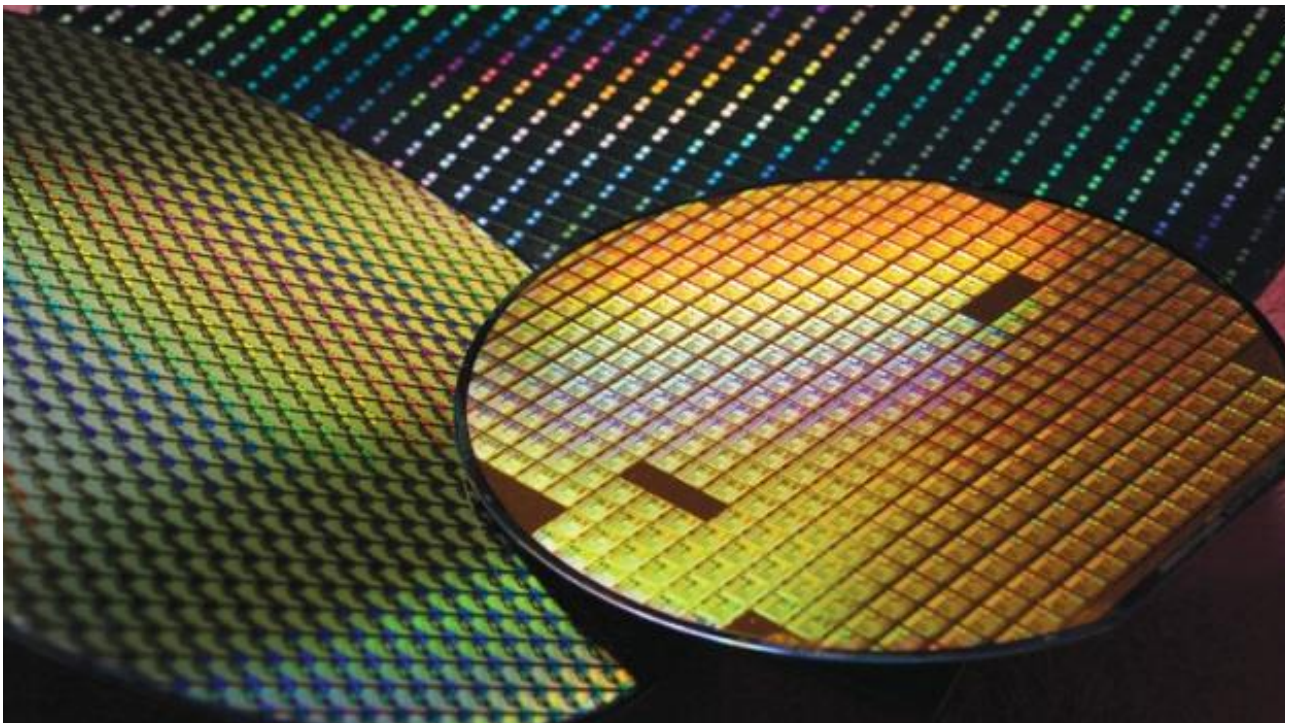


MSE 160 – Semiconductor characterization

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Outline

Semiconductor wafer synthesis

Semiconductor resistivity measurement

Final presentation Q & A

62

Modern computers use single crystal Si wafer substrates



63

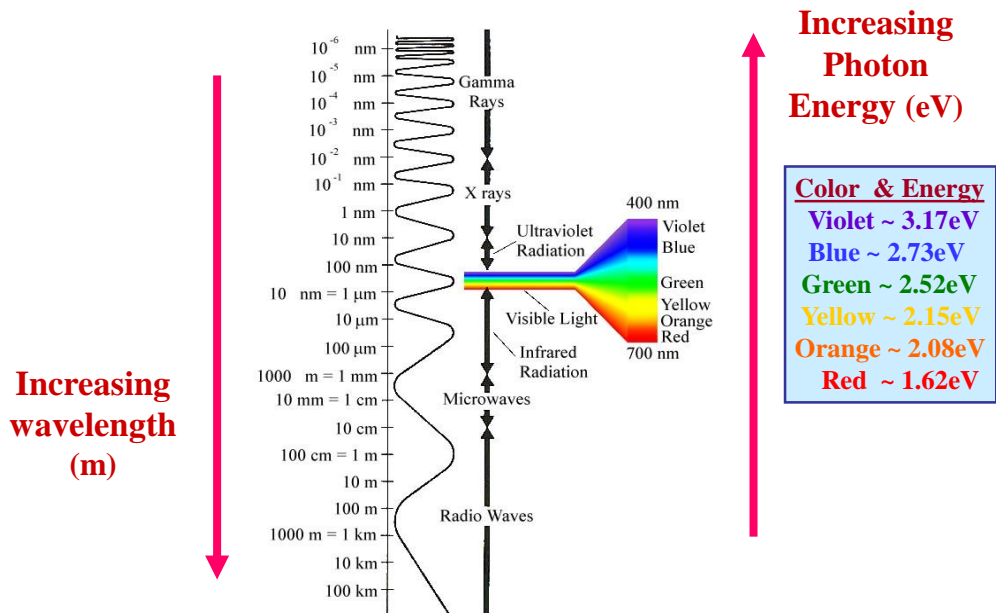
Modern computers use single crystal Si wafer substrates



Why is Si black?

64

Semiconductors can have bandgap in the visible range



65



Home » Science & Innovation » Energy Sources » Solar

The tremendous growth in the U.S. solar industry is helping to pave the way to a cleaner, more sustainable energy future. Over the past few years, the cost of a solar energy system has dropped significantly -- helping to give more American families and business access to affordable, [clean energy](#).

Through a portfolio of R&D efforts, the Energy Department remains committed to leveraging America's abundant solar energy resources -- driving research, manufacturing and market solutions to support widespread expansion of the nation's solar market.

Solar Energy Technologies Office
Solar Energy Technologies Office Homepage
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66

Solar Cell Manufacturing

SUN: 20 TW/ PER HOUR

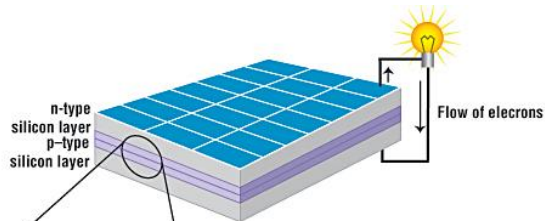
EARTH USES: 16 TW/ PER YEAR

ENERGY

0:16 / 2:56

67

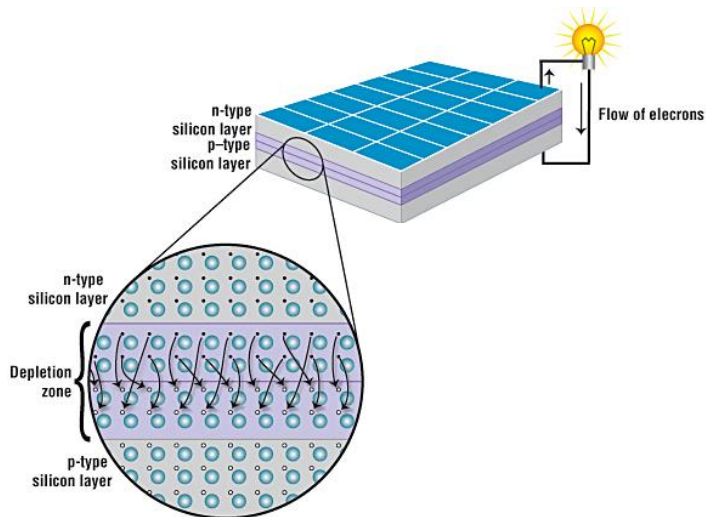
A photovoltaic cell is a p-n junction



Anthony Fernandez "How a Solar Cell Works"
American Chemical Society, acs.org

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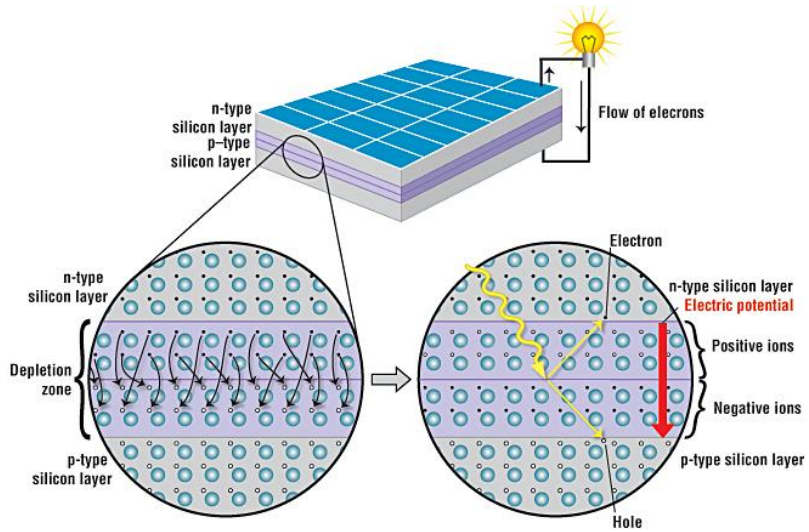
A photovoltaic cell is a p-n junction



Anthony Fernandez "How a Solar Cell Works"
American Chemical Society, acs.org

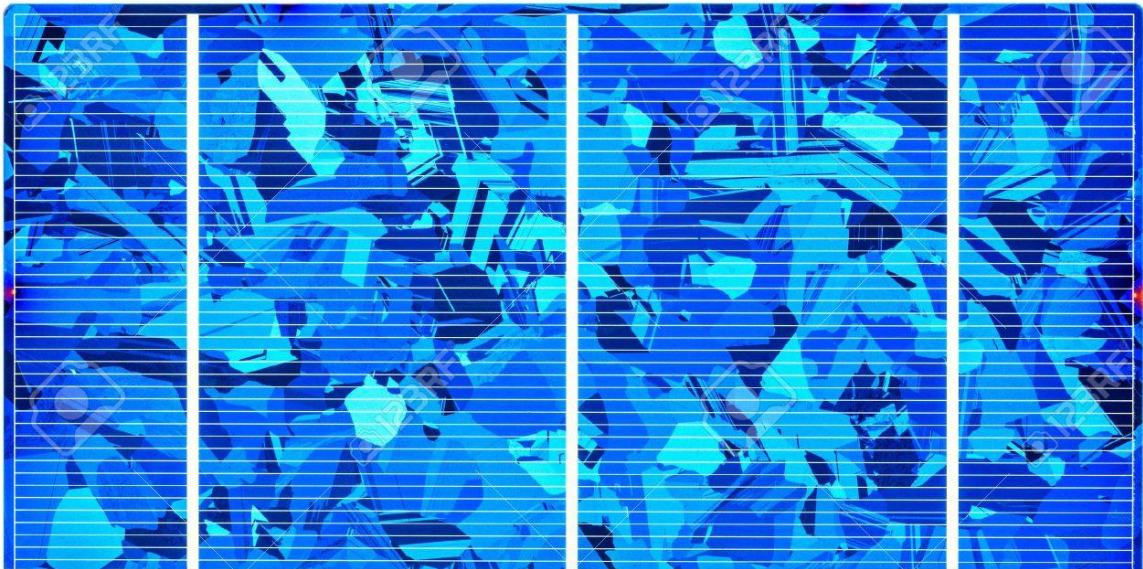
69

A photovoltaic cell is a p-n junction

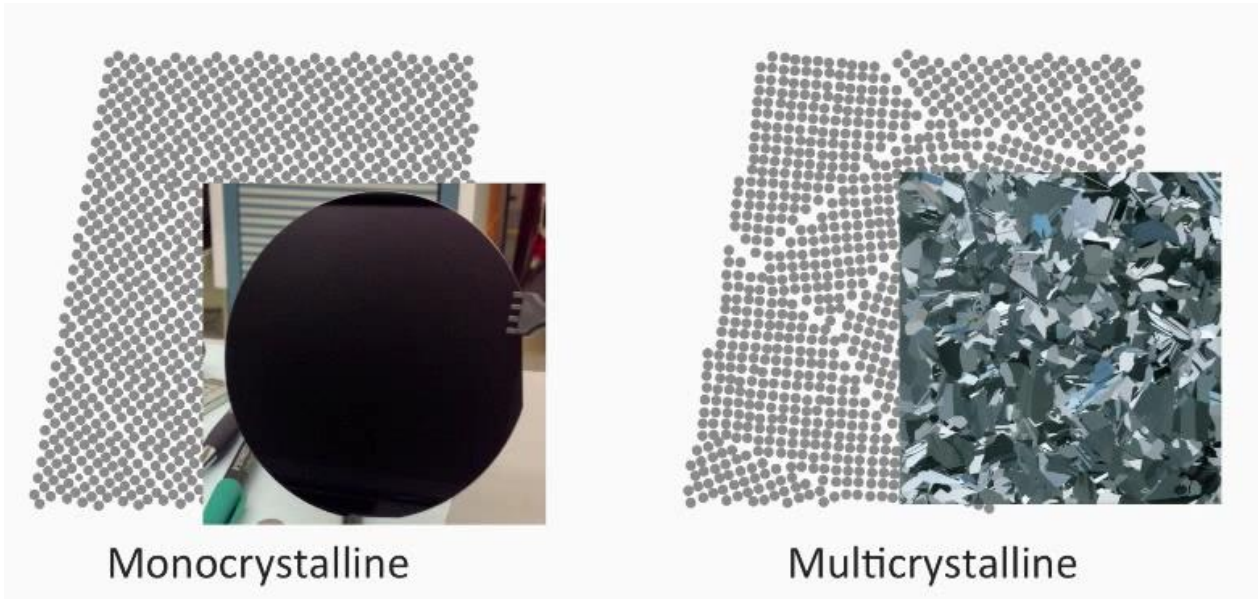


Anthony Fernandez "How a Solar Cell Works"
American Chemical Society, acs.org

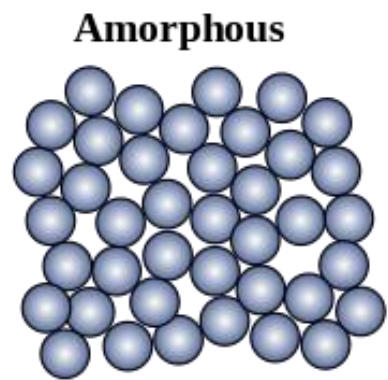
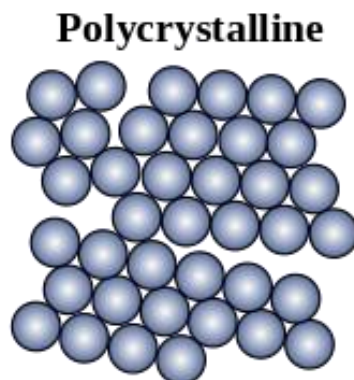
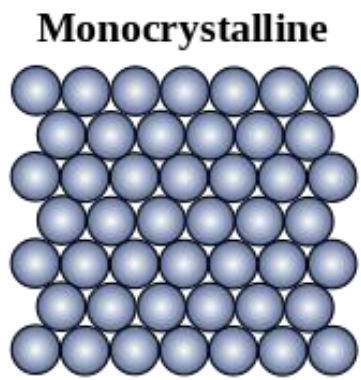
70



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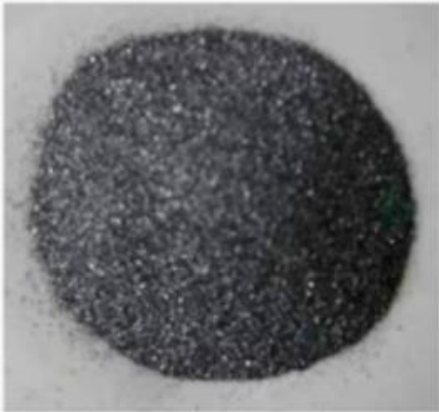
72



73

Si manufacturing is grounded in materials synthesis

Metallurgical silicon



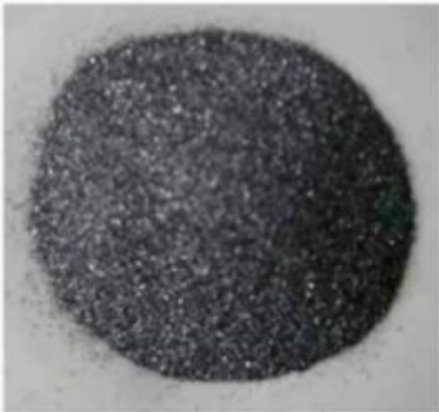
70% of mg-si is for Al alloying for automotive.
30% for other Si for e.g. silicones.
1% for poly and mono Si

74

Solar Energy - DelftX - Arno Smets

Si manufacturing is grounded in materials synthesis

Metallurgical silicon



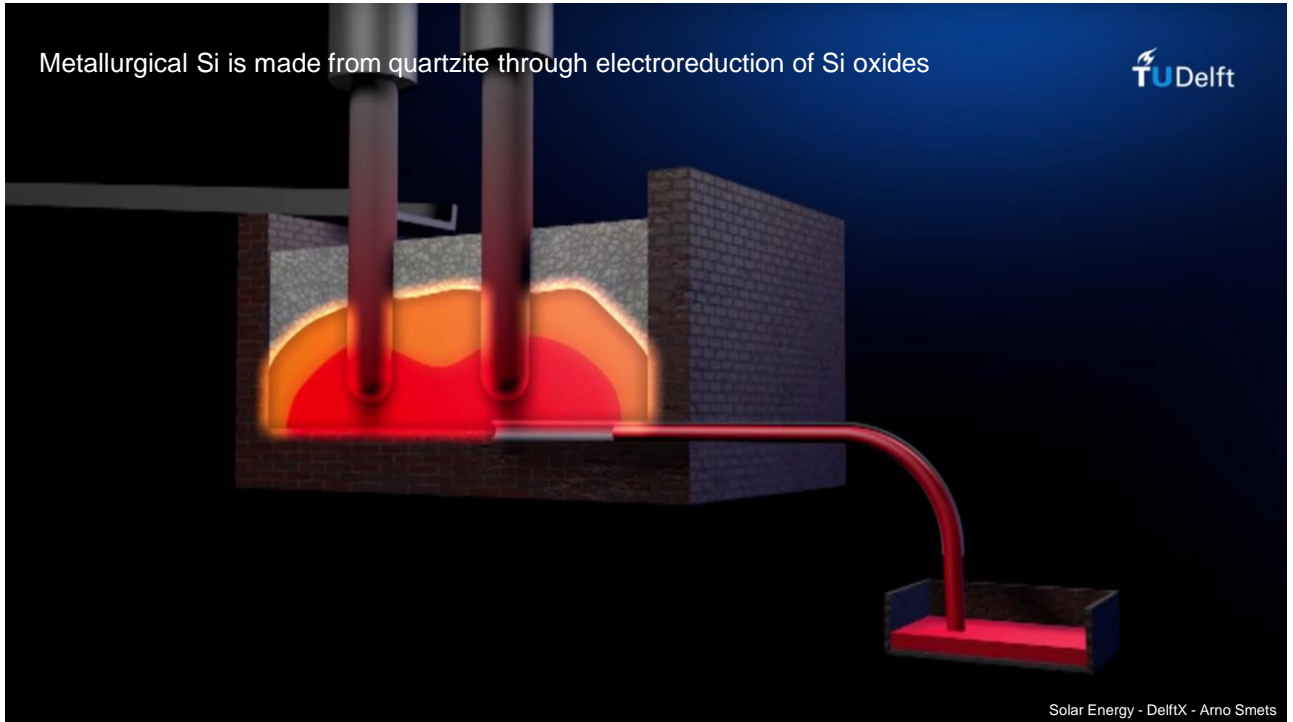
Polycrystalline silicon



75

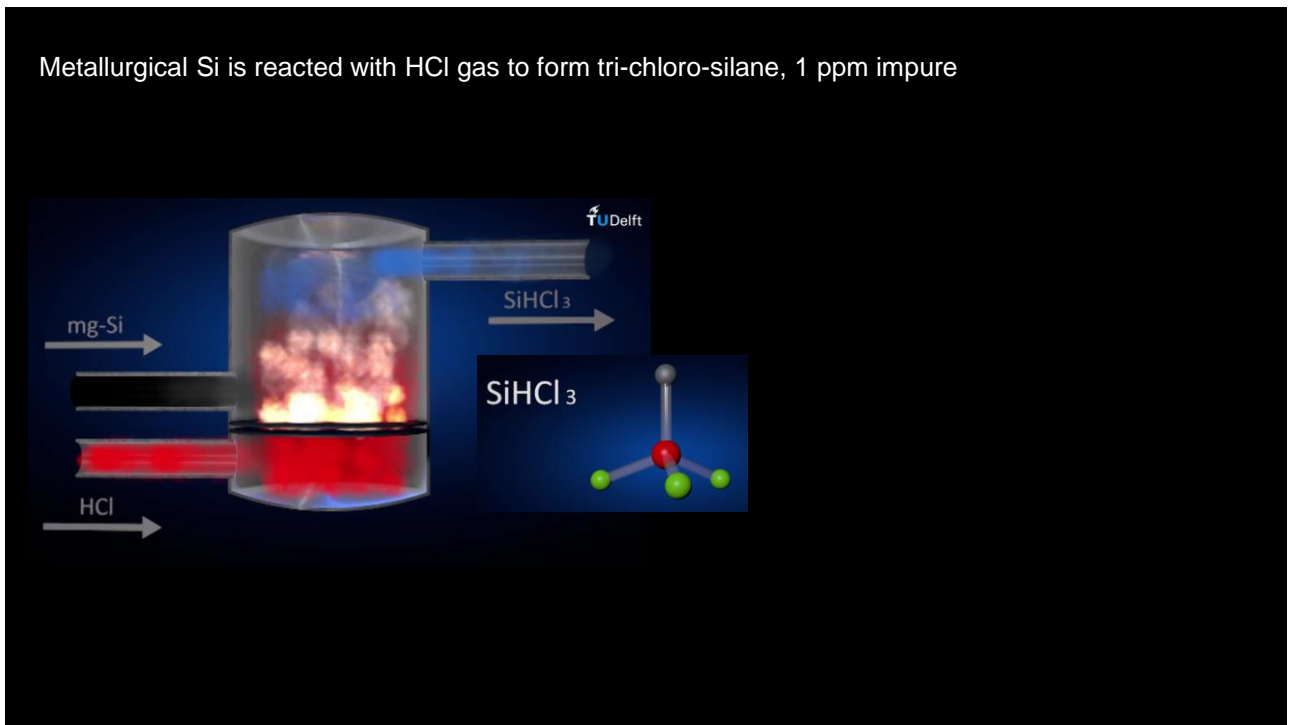
Solar Energy - DelftX - Arno Smets

Metallurgical Si is made from quartzite through electroreduction of Si oxides



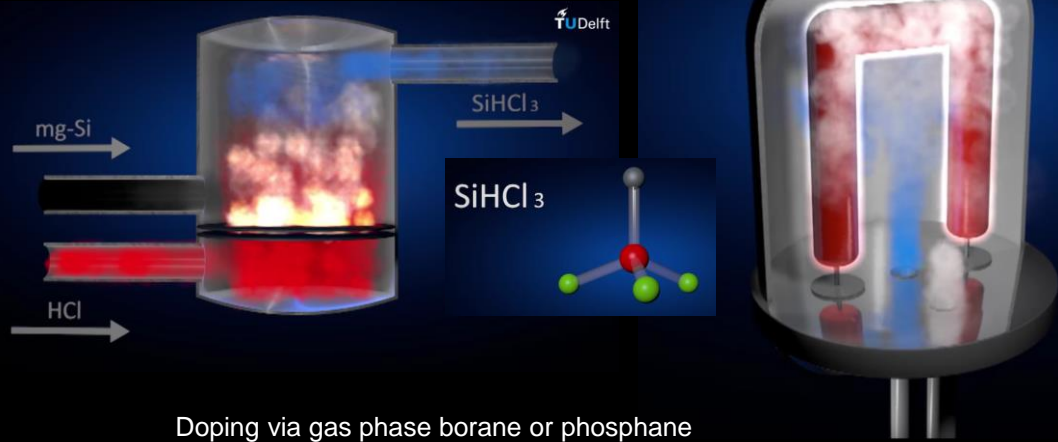
76

Metallurgical Si is reacted with HCl gas to form tri-chloro-silane, 1 ppm impure



77

Polycrystalline Si (1 ppm) is made from metallurgical Si by chemical vapor deposition

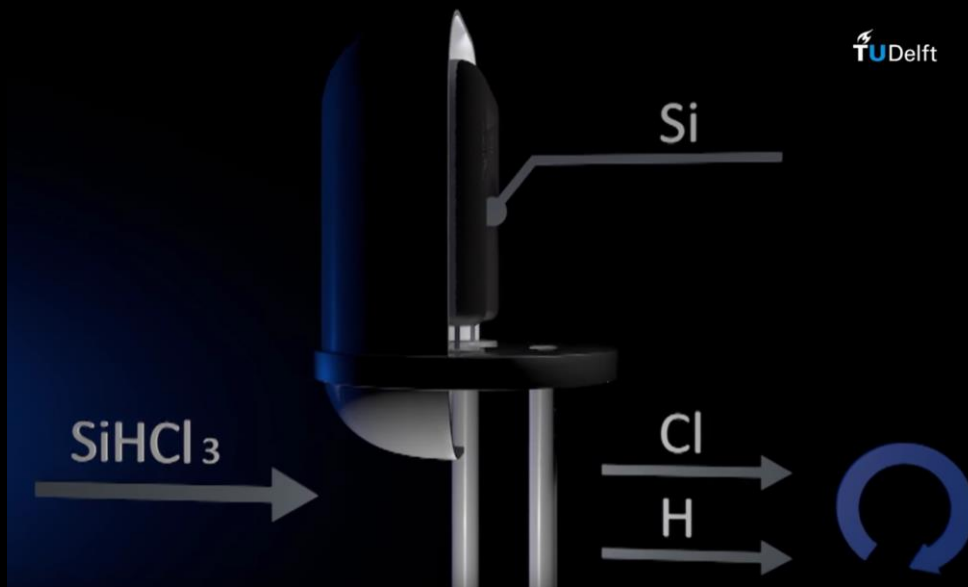


Doping via gas phase borane or phosphane

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78

Polycrystalline Si (1 ppm) is made from metallurgical Si by chemical vapor deposition



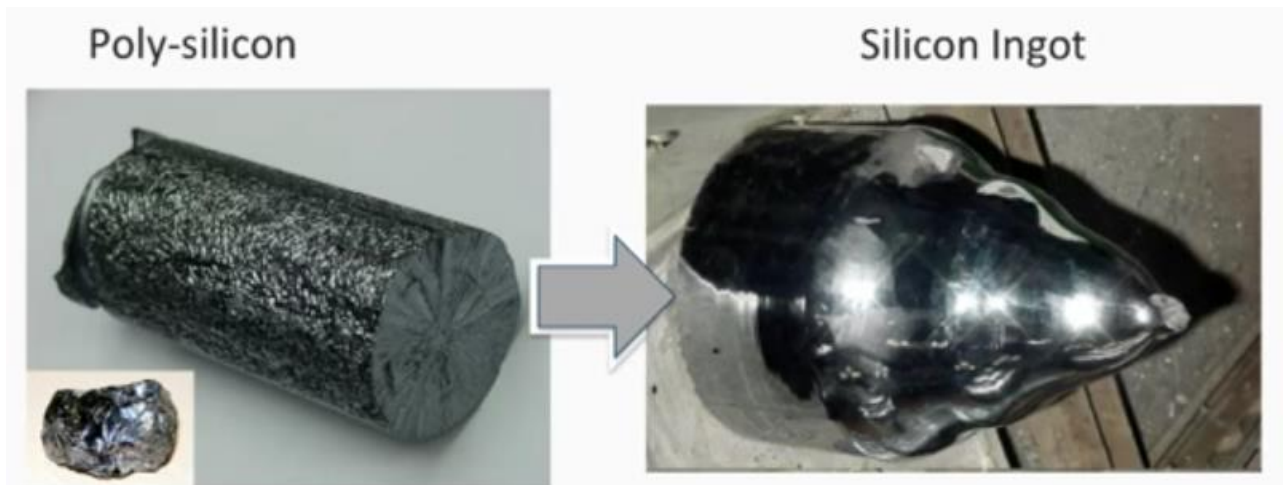
79

Modern computers use single crystal Si wafer substrates



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Si ingot is prepared from poly Si



https://www.youtube.com/watch?v=8QKzS_wKo0&t=320s

81

Multicrystalline ingot is also produced from melt by directional solidification



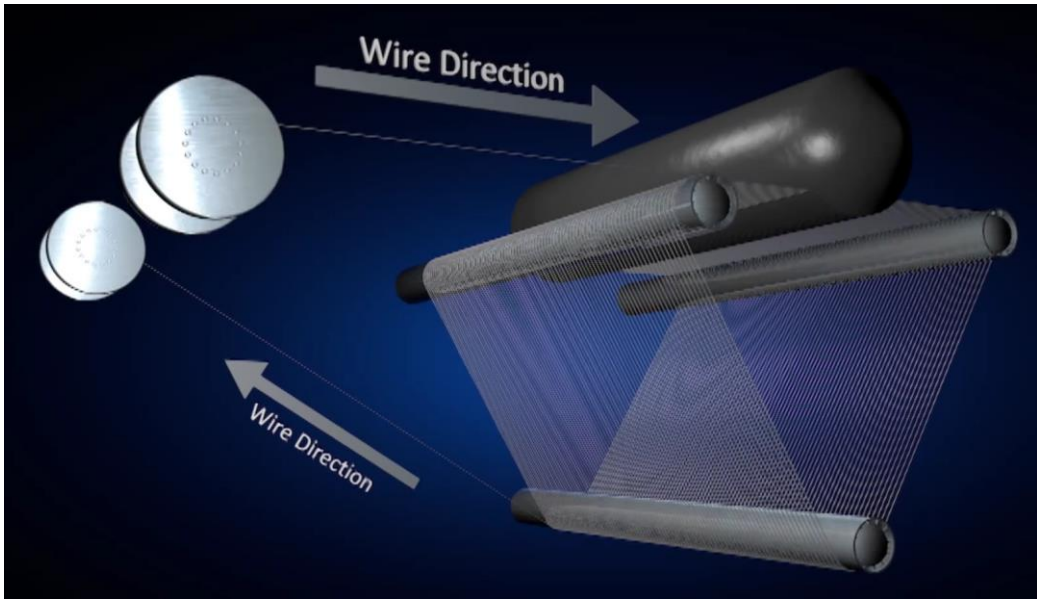
82

Multicrystalline ingot is produced from melt



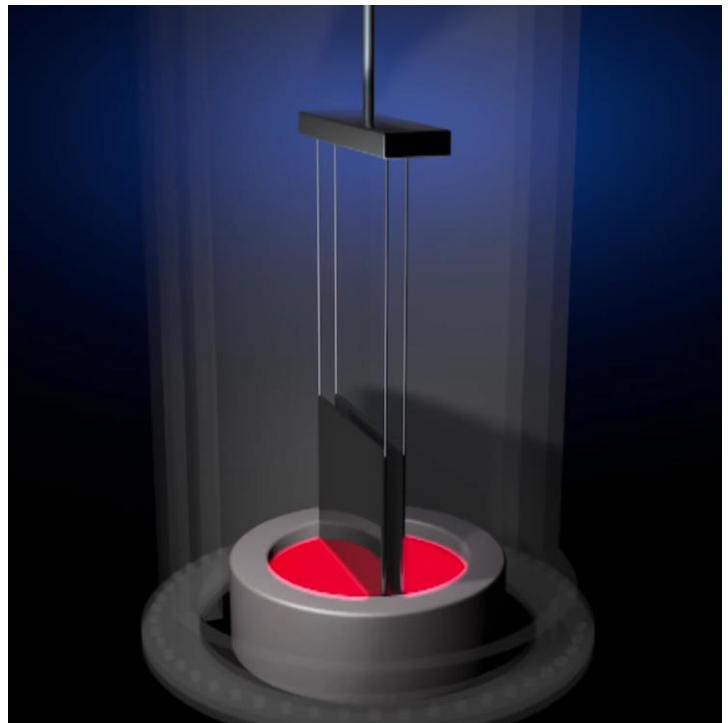
83

Wafers are created from ingot via sawing to $\sim 150 \mu\text{m}$



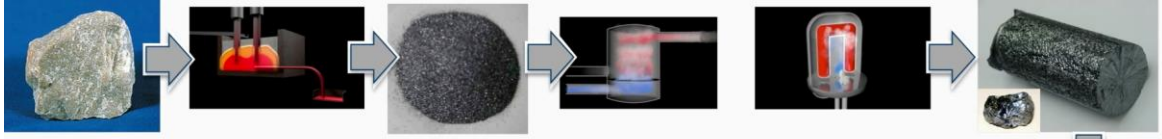
84

Wafers are created from Si ribbon



85

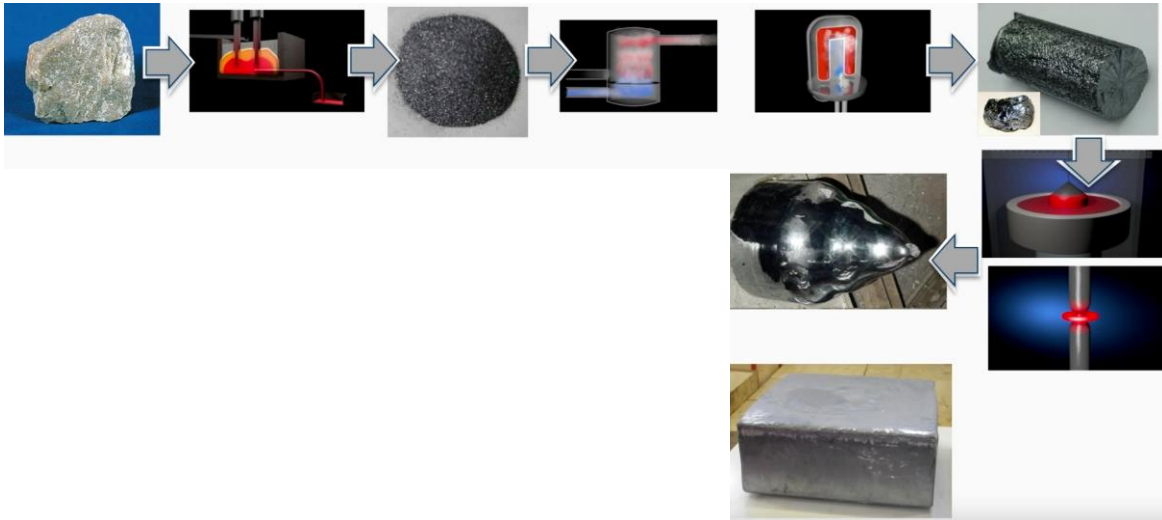
Si manufacturing is grounded in materials synthesis



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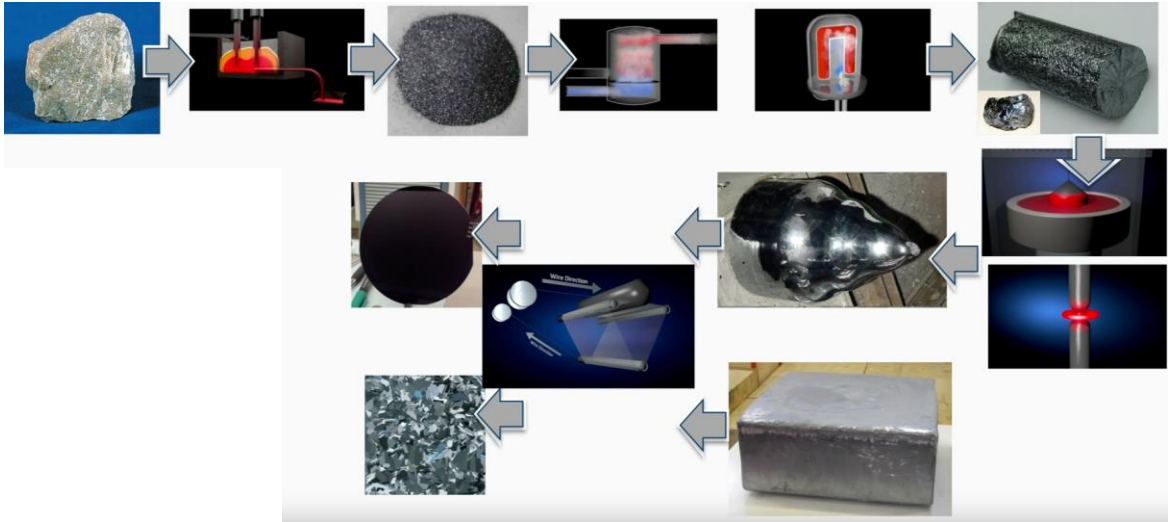
Solar Energy - DelftX - Arno Smets

Si manufacturing is grounded in materials synthesis



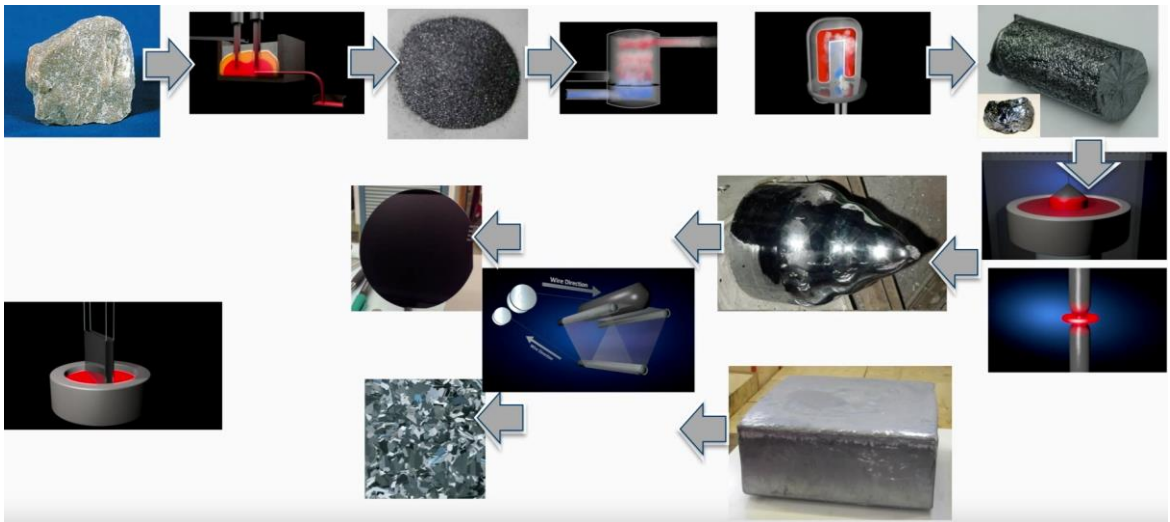
87

Si manufacturing is grounded in materials synthesis



88

Si manufacturing is grounded in materials synthesis



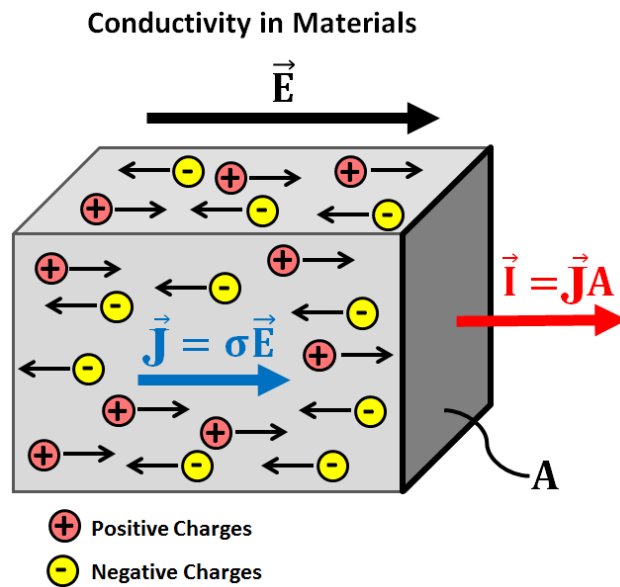
89

Conductivity of semiconductor increases with temperature

How does this differ from metal? What happens in metals as T increases?

90

Conductivity of semiconductor increases with temperature



91

Conductivity of semiconductor increases with temperature

- Electrical conductivity, $\sigma = 1/\rho = \sum_i(nq\mu)_i$
- i = carrier (e.g. electron, hole, ion)
- n = carrier concentration
- q = carrier charge
- μ = carrier mobility

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Conductivity of semiconductor increases with temperature

- Electrical conductivity, $\sigma = 1/\rho = \sum_i(nq\mu)_i$
- i = carrier (e.g. electron, hole, ion)
- n = carrier concentration
- q = carrier charge
- μ = carrier mobility
- With increasing temperature
 - q does not change
 - μ decreases (because of drift velocity)
 - n increases exponentially

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Conductivity of semiconductor increases with temperature

- Carrier concentration depends exponentially on temperature

Electron density in conduction band Conduction band minimum Fermi level

$$n_0 = N_c \exp\left[-\frac{E_c - E_F}{k_B T}\right]$$

Conduction band states

94

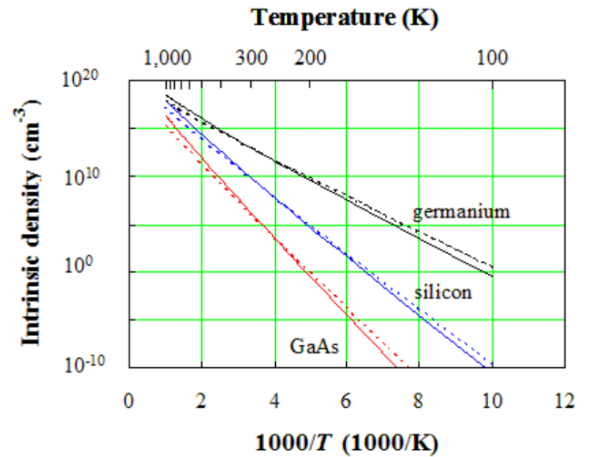
Conductivity of semiconductor increases with temperature

- Carrier concentration depends exponentially on temperature

Electron density in conduction band Conduction band minimum Fermi level

$$n_0 = N_c \exp\left[-\frac{E_c - E_F}{k_B T}\right]$$

Conduction band states



95

Conductivity of semiconductor increases with temperature

- Carrier concentration depends exponentially on temperature

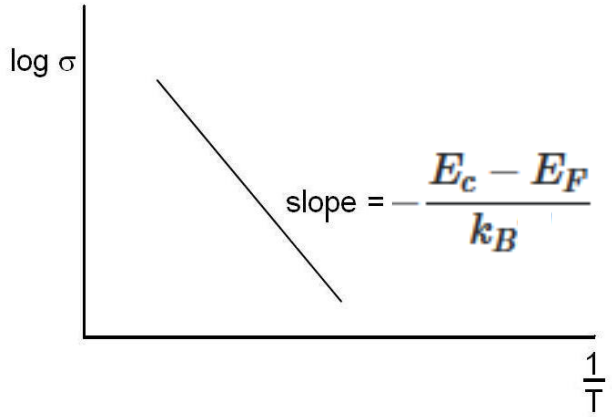
Electron density in conduction band

Conduction band minimum

Fermi level

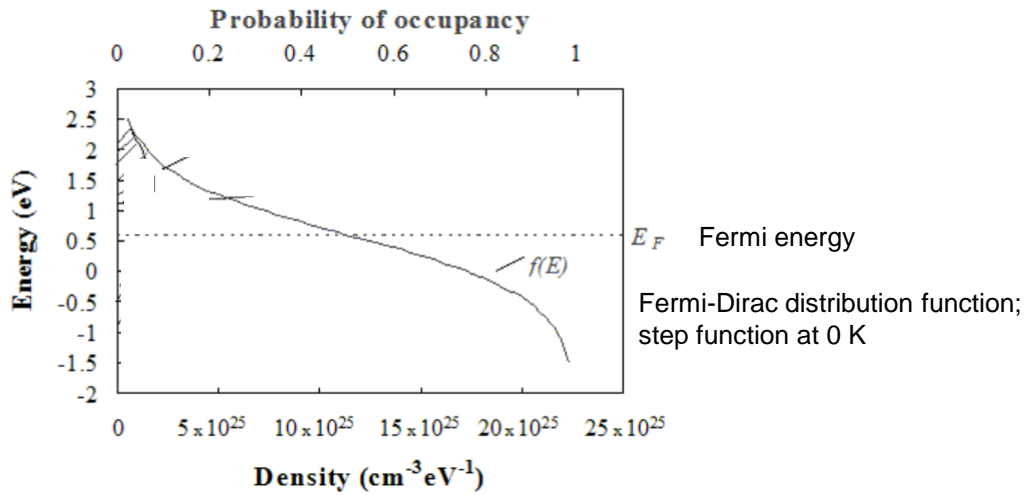
$$n_0 = N_c \exp\left[-\frac{E_c - E_F}{k_B T}\right]$$

Conduction band states



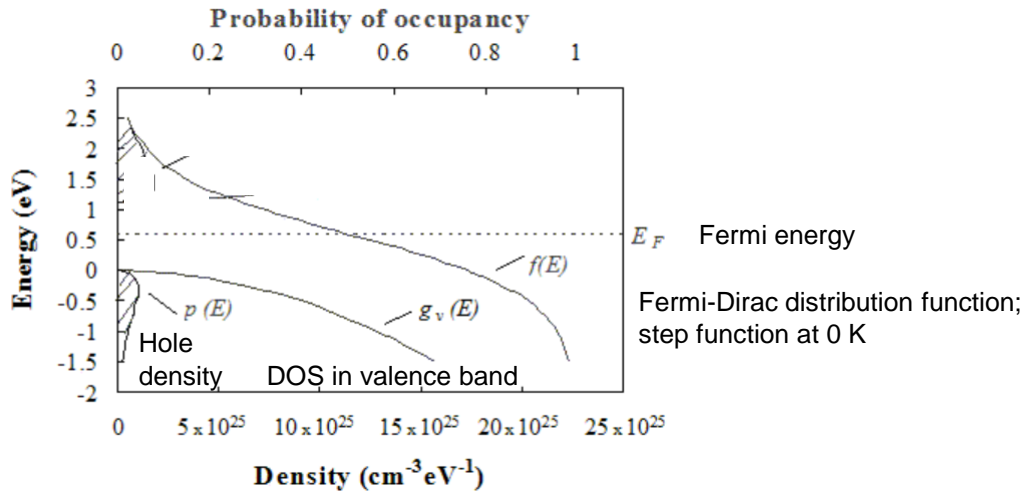
96

Calculation of the electron and hole density in a semiconductor



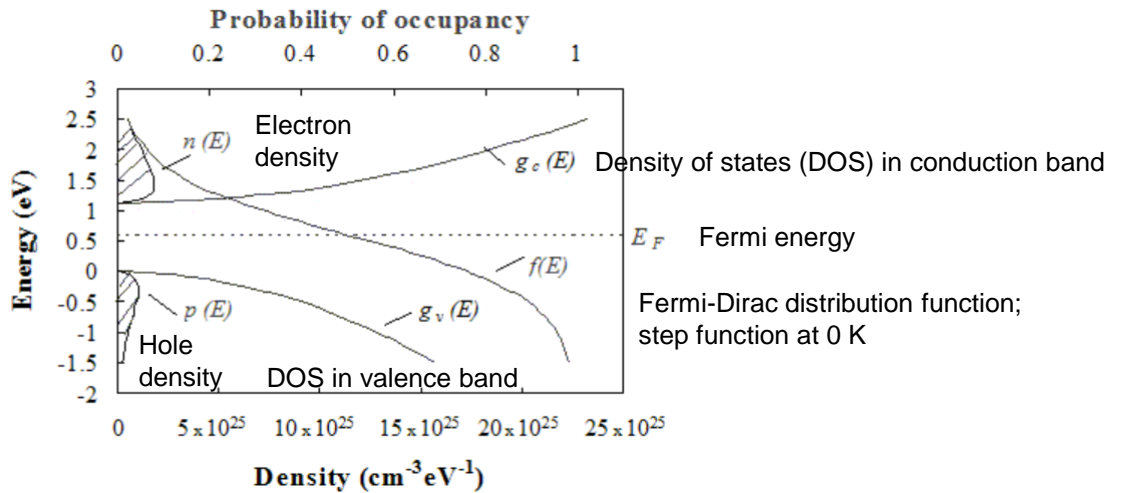
97

Calculation of the electron and hole density in a semiconductor



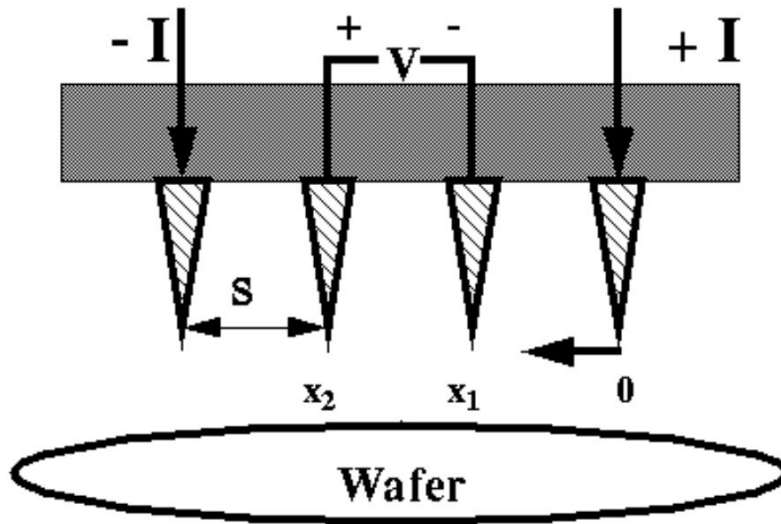
98

Calculation of the electron and hole density in a semiconductor



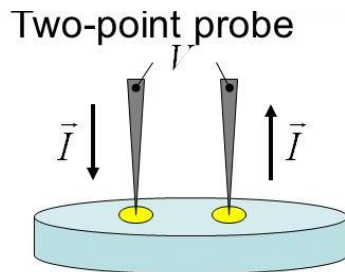
99

4-point probe measures the resistivity of any semiconductor



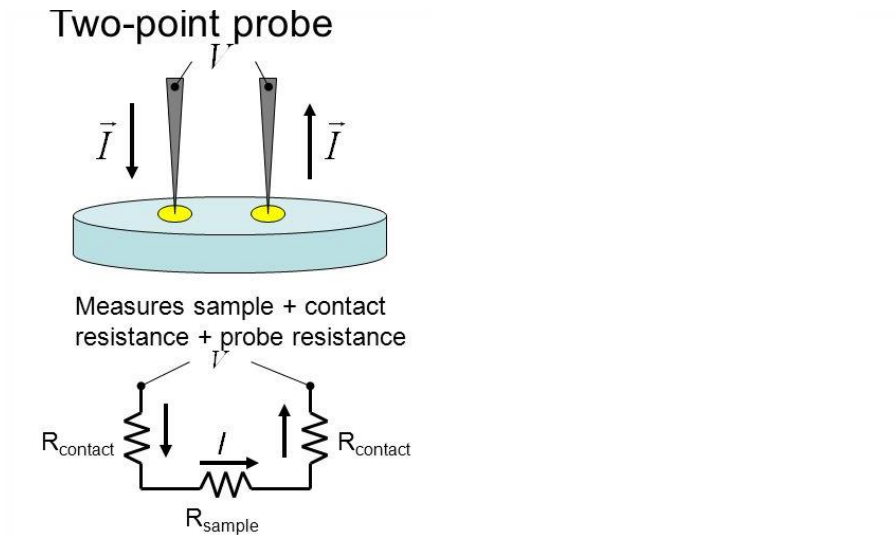
100

2-point probe measures sample, contact and probe resistance



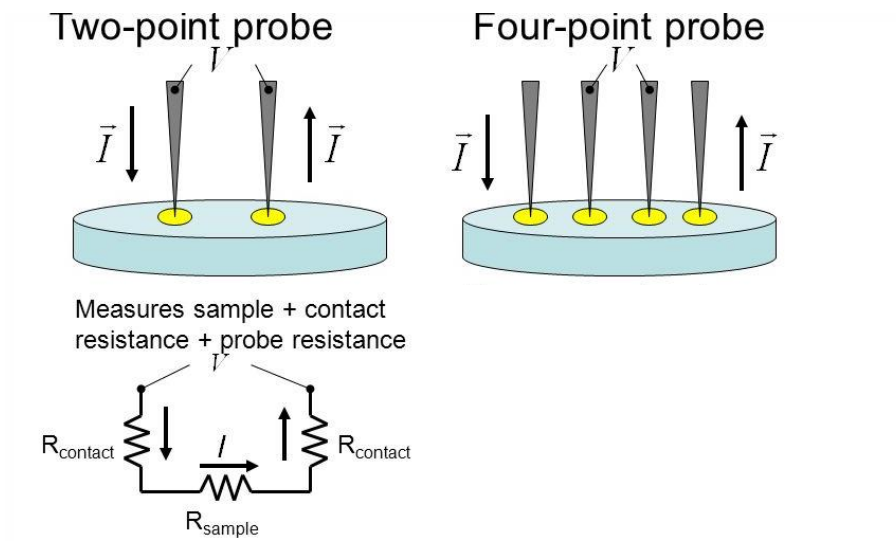
101

2-point probe measures sample, contact and probe resistance



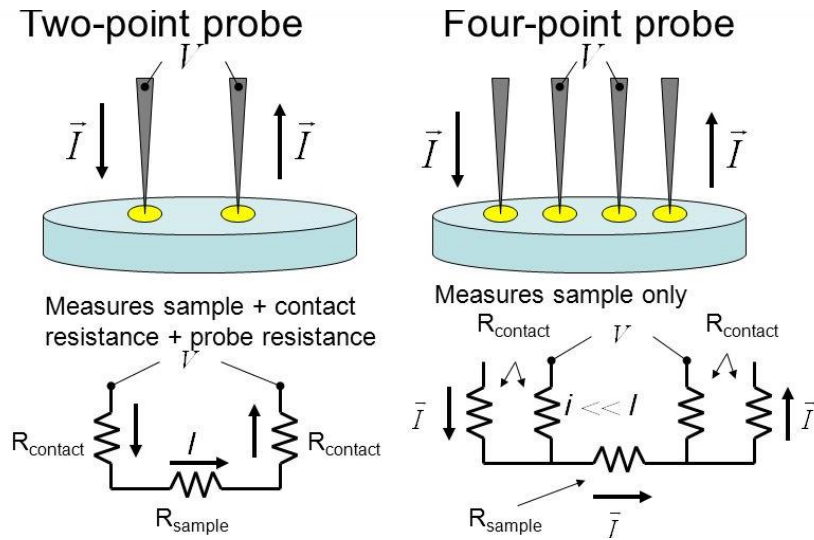
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4-point probe measures sample only



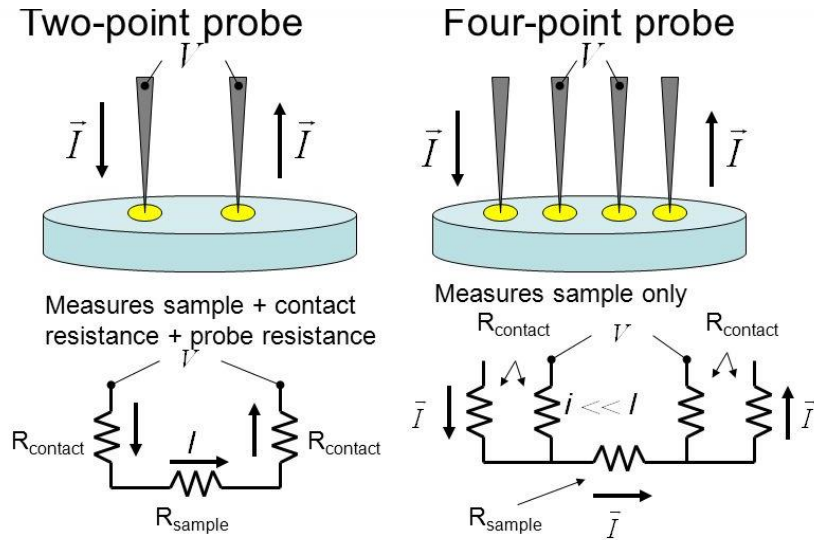
103

4-point probe measures sample only



104

4-point probe measures sample only



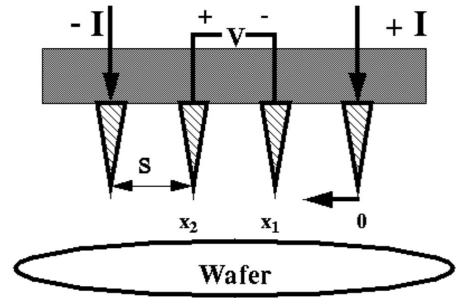
In four-point probe, negligible current flows through the voltmeter, the only voltage drop measured is across R_{sample} .

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4-point probe method applies to bulk and thin films

- For bulk samples, thickness $t \gg s$
- Assume spherical protrusion of current emanating from the outer probe tips
- The differential resistance is:

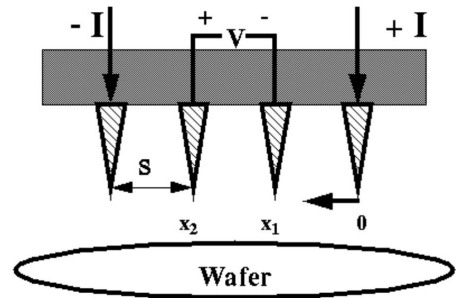
$$\Delta R = \rho \left(\frac{dx}{A} \right)$$



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4-point probe method applies to bulk and thin films

- Integration between the inner probe tips (where the voltage is measured)
- Assume spherical protrusion of current emanating from the outer probe tips



$$R = \int_{x_1}^{x_2} \rho \frac{dx}{2\pi x^2} = \frac{\rho}{2\pi} \left(-\frac{1}{x} \right) \Big|_{x_1}^{x_2} = \frac{1}{2s} \frac{\rho}{2\pi}$$

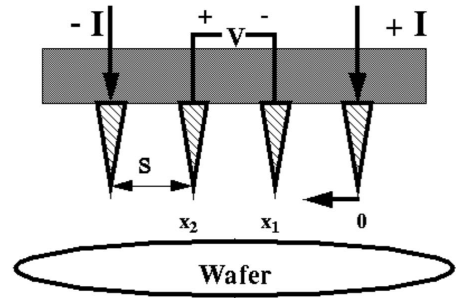
Half sphere

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4-point probe method applies to bulk and thin films

- superposition of current at the outer two tips: $R = V/2I$
- the expression for bulk resistivity

$$\rho = 2\pi s \left(\frac{V}{I} \right)$$



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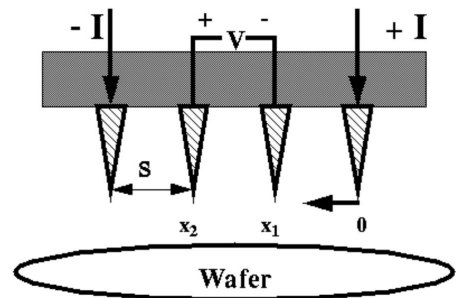
4-point probe method applies to bulk and thin films

- For thin layers with thickness $t \ll s$
- Current rings instead of spheres emanate from the outer probe tips

• The area is thus: $A = 2\pi x t$

- The resistance is:

$$R = \int_{x_1}^{x_2} \rho \frac{dx}{2\pi x t} = \int_s^{2s} \frac{\rho}{2\pi t} \frac{dx}{x} = \frac{\rho}{2\pi t} \ln(x) \Big|_s^{2s} = \frac{\rho}{2\pi t} \ln 2$$



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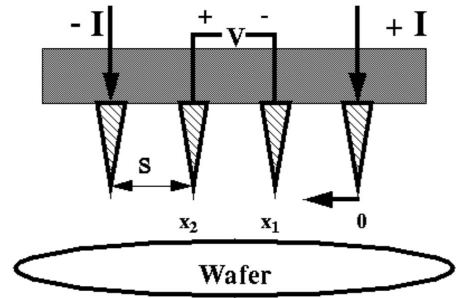
4-point probe method applies to bulk and thin films

- superposition of current at the outer two tips: $R = V/2I$

$$\rho = \frac{\pi t}{\ln 2} \left(\frac{V}{I} \right)$$

- Sheet resistivity is per thickness

$$R_s = \rho/t = \frac{\pi}{\ln 2} \left(\frac{V}{I} \right)$$



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Final presentations are next M-W, any questions?

		characterization		
Week 10	M/W Group 1 final presentations	T/Th Groups 1 & 2 final presentations	M/W Group 2 final presentations	No Lab
3/9 - 3/12		No Lecture		No Lecture
Week 11			M/W Groups semiconductor lab reports due by 1 PM PST	T/Th Groups semiconductor lab reports due by 1 PM PST
3/14 - 3/20				

111

References (see Class page)

Semiconductors

B. Van Zeghbroeck (2011) Principles of Semiconductors

https://ecee.colorado.edu/~bart/book/book/chapter2/ch2_6.htm#fig2_6_5

Four-point probe

Chan J Friedberg P (2002) Four point probe manual

Silicon wafer synthesis

Throughout